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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

KURITA, et al.

Serial No. 09/464,362

Filed: December 15, 1999

For: DUAL SUBSTRATE LOADLOCK
PROCESS EQUIPMENT

Group Art Unit: 1763

Examiner: McArthur, S.

H7A
10/20/01
MW

Assistant Commissioner of Patents
Washington, D.C. 20231

AMENDMENT

RECEIVED
OCT 19 2001
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Dear Sirs:

This is in response to the Office Action dated April 11, 2001, which was Paper No. 5 of the present application, response to which is due October 11, 2001 by the enclosed Petition for Extension of Time. Please amend the present application as follows:

IN THE CLAIMS:

Please cancel claims 1-21, 31, 33-37, and 43-97 without prejudice.

Please amend claims 38-42 as follows:

11/ ~~38~~. (amended)

A substrate processing system comprising:

at least one processing chamber;

a transfer chamber connected to said at least one processing chamber; and

a loadlock connected to said transfer chamber, said loadlock comprising:

a single substrate upper support and a single substrate lower support;

a transfer aperture to transfer a single substrate between said transfer chamber and said loadlock;

an elevator to raise and lower said single substrate upper support and said single substrate lower support;

a cooling plate disposed in said loadlock and positioned to accept a single substrate from said single substrate lower support;

a load/unload aperture through which an unprocessed substrate may be

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